Plasma Processing of fullerene C₆₀ for industrial applications

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collaboration with G. Palazzo and H. Mateos Cuadrado

Experimental Section

Results

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UV-Vis spectroscopy on filtered dispersion

- Main band of absorption: 355nm
- Wide band at 500nm: C_{60} water complexes
- Significant increase in Abs in comparison to control sample
- No net trend with treatment time and power





80W, 20'	81.2	18.8	grafted	
80W, 5′	82.7	17.3		•
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• Further investigations necessary

• Plasma treatment efficient in producing better				
dispersion of C ₆₀				
• Negative ζ POTENTIAL. The colloidal dispersion is				
stable.				
• ζ POTENTIAL is lower than pristine C ₆₀ dispersion:				

dicative of negatively charged groups

AEROSOL-ASSISTED ATMOSPHERIC PRESSURE PLASMA DEPOSITION OF C_{60}/TiO_{2} **NANOCOMPOSITE COATINGS** - in collaboration with R. Comparelli and M.L. Curri



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- Methylene blue 10⁻⁵M is used as model pollutant and photodegraded under UV lamp (λ>250nm, 30W)
- 15' of conditioning before photodegradation test